

A B S T R A C T

AN ION IMPLANTER POWER SUPPLY DESIGNED TO LIMIT THE
CHARGE EFFECT

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The invention relates to a power supply ALT for an
ion implanter, the power supply comprising:

- an electricity generator SOU placed between a
substrate-carrier tray PPS and ground E; and

10 · a capacitor CDS in a parallel branch likewise
connected between the substrate-carrier tray PPS and
ground E.

The capacitor CDS has a capacitance of less than 5 nF.

The invention also provides an ion implanter

15 incorporating the power supply.

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35 Translation of the title and the abstract as they were when originally filed by the
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38.2, and/or 48.3.